

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Withdrawn) An array substrate for a liquid crystal display device, comprising:
a substrate having a non-display region and a display region;
a plurality of gate and data lines crossing each other on the substrate;
a gate electrode connected to one of said gate lines;
a gate insulating layer on the gate line and the gate electrode;
an active layer on the gate insulating layer over the gate electrode;
an ohmic contact layer on the active layer;
source and drain electrodes spaced apart from each other on the ohmic contact layer;
a pixel electrode connected to the drain electrode and contacting the gate insulating layer;
an alignment layer on the pixel electrode;
gate and data pads defined as an end portion of the gate and data lines, respectively, said gate and data pads positioned at the non-display region; and
gate and data pad terminals on the gate and data pads, respectively.
2. (Withdrawn) The array substrate according to claim 1, wherein the data pad terminal extends to the display region.
3. (Withdrawn) The array substrate according to claim 1, wherein a data pad terminal comprises the same material as the pixel electrode.
4. (Withdrawn) The array substrate according to claim 1, wherein the alignment layer comprises polyimide.

5-17. (Cancelled)

18. (Previously Presented) A method of manufacturing an array substrate for a liquid crystal display device comprising:

forming a thin film transistor having a gate electrode, source and drain electrodes, an active layer, and an ohmic contact layer;

forming a pixel electrode contacting the drain electrode,

wherein the formation of at least one of the electrodes, the active layer, and the ohmic contact layer are processed by a photolithography method using photoresists,

wherein the ohmic contact layer is etched by a dry etching process in a chamber, and

wherein a photoresist used in the formation of the ohmic contact layer is removed by a dry strip method using dry gases in the chamber and wherein an upper surface of the ohmic contact layer is etched after the dry strip method.

19. (Original) The method according to claim 18, wherein the dry gases used in the dry strip include O₂ as a base gas and SF₆ or CF₄ as a reactive gas.

20. (Cancelled).

21. (Previously Presented) The method according to claim 18, wherein the upper surface of the ohmic contact layer is etched to a depth of between 100 and 700 Angstroms.

22. (Original) The method according to claim 21, wherein a thickness of the ohmic contact layer before etching is between about 400 and about 1,000 Angstroms.

23. (Withdrawn) A liquid crystal display device, comprising:

a gate electrode on a substrate having a display region and a non-display region;

a gate insulating layer on the gate electrode;

an active layer and an ohmic contact layer on the gate insulating layer over the gate electrode;

source and drain electrodes;
a pixel electrode contacting the drain electrode on the gate insulating layer;
an alignment layer on the pixel electrode and the source and drain electrodes;
a data line connected to the source electrode and having a data pad at the non-display region; and
a data pad terminal directly contacting the data pad and contacting and extending below a seal pattern between two substrates.